

ABSTRACT

When a mask blank substrate is gripped by a transport robot, a pressure is prevented from being locally generated to suppress dust generation from a gripper.

- 5 A mask blank substrate 10 comprises: first and second main surfaces 12a and 12b; four side faces 16a to 16d; first to fourth chamfered faces 18a to 18d that are formed between the first main surface 12a and the four side faces 16a to 16d; and fifth to eighth chamfered faces 18a' to 18d' that are formed between the second main surface 12b and the four side faces 16a to 16d. On a cross section A substantially
- 10 perpendicular to the first and second main surfaces 12a and 12b and to the two side faces 16a and 16c, when the seventh chamfered face 18c' serves as a reference plane Pc', a parallelism of a contour La of the first chamfered face 18a, which is diagonally opposite to the seventh chamfered face 18c', is 0.02 mm or less, and when the first chamfered face 18a serves as a reference plane Pa, a parallelism of a contour Lc' of the
- 15 seventh chamfered face 18c' is 0.02 mm or less.